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APPLICATION NO.	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/689,348		10/20/2003	Stephan Grunow	TI-36564	4206
23494	7590	09/08/2006		EXAM	INER
TEXAS IN	STRUM	ENTS INCORPOR	FARAHAI	FARAHANI, DANA	
P O BOX 655474, M/S 3999 DALLAS, TX 75265				ART UNIT	PAPER NUMBER
DALLAS,	IA 1320	3	2891		
			DATE MAILED: 09/08/2006		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)				
C	Office Action Summary	10/689,348 Examiner	GRUNOW ET AL. Art Unit				
_	• • • • • • • • • • • • • • • • • • •						
Thi	MAILING DATE of this communication and	Dana Farahani	orrespondence address				
	The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply						
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).							
Status							
1)⊠ Res	ponsive to communication(s) filed on <u>07 Ju</u>	<u>ıne 2006</u> .					
2a)∐ This	This action is FINAL . 2b)⊠ This action is non-final.						
3)☐ Sinc	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
close	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Disposition o	f Claims						
4) Claim(s) 1-3 and 5-16 is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration. 5) Claim(s) is/are allowed. 6) Claim(s) 1-3 and 5-16 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or election requirement.							
Application Papers							
9) The specification is objected to by the Examiner. 10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner. Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a). Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.							
Priority under	r 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 							
2) Notice of D 3) Information	deferences Cited (PTO-892) Praftsperson's Patent Drawing Review (PTO-948) In Disclosure Statement(s) (PTO-1449 or PTO/SB/08)	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:					

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DETAILED ACTION

1. In view of the appeal brief filed on 2/22/05, PROSECUTION IS HEREBY REOPENED.

New grounds of rejection are set forth below.

To avoid abandonment of the application, appellant must exercise one of the following two options:

(1) file a reply under 37 CFR 1.111 (if this Office action is non-final) or a reply under 37 CFR 1.113 (if this Office action is final); or,

(2) request reinstatement of the appeal.

If reinstatement of the appeal is requested, such request must be accompanied by a supplemental appeal brief, but no new amendments, affidavits (37 CFR 1.130, 1.131 or 1.132) or other evidence are permitted. See 37 CFR 1.193(b)(2).

Claim Objections

2. Claim 5 is objected to under 37 CFR 1.75(c), as being of improper dependent form for failing to further limit the subject matter of a previous claim. Applicant is required to cancel the claim, or amend the claim to place the claim in proper dependent form, or rewrite the claim in independent form. Specifically, the limitation that of the ratio X1 to X2 is greater than 3 to 2 is already in the parent claims.

Claim Rejections - 35 USC § 103

3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

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(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which the subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

4. Claims 1-3 and 6-16 are rejected under 35 U.S.C. 103(a) as being unpatentable over Cohen (US Patent 6,518,668) in view of Satta et al., hereinafter Satta (US Application Publication 2004/0121616).

Regarding claim 1, Cohen discloses in figure 1, an integrated interconnect structure comprising a dielectric layer 12 over a semiconductor 10; a first trench formed in the dielectric layer, the trench having sidewalls; a first contiguous barrier layer 18 formed to a thickness x1 over the upper surface of the dielectric layer and formed to a thickness x2 on the trench sidewalls wherein x1 is greater than x2 with a ration of 3 to 2 (see col. 7, lines 3 and 4), and copper over the first barrier layer (col. 6, line 46).

Cohen does not disclose the dielectric layer is a low K dielectric.

Satta discloses in figures 1 that the dielectric of an interconnect structure whose barrier layer can be made with the same process as that of the Cohen reference, namely CVD, has low K dielectric (see paragraph 33). Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention to make the dielectric layer of the Cohen reference a low K dielectric in order to reduce the parasitic capacitance of that interconnect structure.

Regarding claims 2, 8, and 12, Cohen in view of Satta renders obvious the claimed invention, as discussed above, also disclosing a second trench (see col. 5, lines 65-66). Although, Cohen does not expressly disclose the second trench spaced apart from the first trench less than 160 nm, it would have been obvious to determine the distance between the trenches to be less than 160, since the trenches are miniaturized, and since the trenches themselves are narrowed to

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about the same range (180 nm), it is possible to make the distance about the same range as that of the opening in the trenches so the resulting structure periodically would have insulators and interconnect plugs, as normally done in the art, and, for example, is shown in figure 1 of Satta.

Regarding claims 3, 7, 10, 11, and 15, Cohen discloses a plurality of trenches, which would have the same barrier layer dimensions as the first trench.

Regarding claim 6, 9, 13, 14, and 16, a second contiguous layer 20 is formed over the first contiguous barrier layer.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Dana Farahani whose telephone number is (571)272-1706. The examiner can normally be reached on M-F 9:00AM - 5:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Bill Baumeister can be reached on (571)272-1722. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

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B. WILLIAM BAUMEISTER SUPERVISORY PATENT EXAMINER

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